

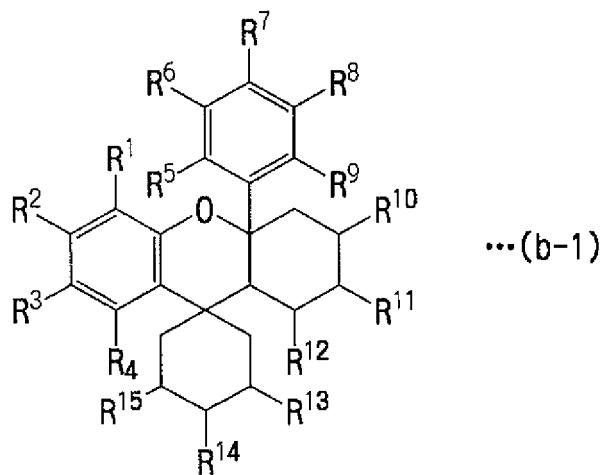
## AMENDMENTS TO THE CLAIMS

### 1-9. (Cancelled)

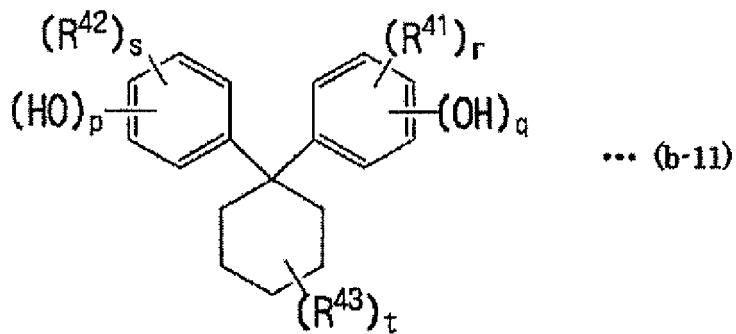
10. (New) A coated substrate comprising a substrate and a photosensitive layer, said photosensitive layer being at least 3  $\mu\text{m}$  in thickness and comprising:

(A) an alkali-soluble novolak resin having a weight average molecular weight of 1,000 to 50,000, in which a portion of hydrogen atoms of phenolic hydroxyl groups are substituted with 1,2-naphthoquinonediazidesulfonyl groups; and

(B) a dissolution promoter comprising at least one compound selected from a group consisting of compounds represented by a general formula (b-1) and a general formula (b-11) shown below:



wherein, R<sup>1</sup> to R<sup>9</sup> each represent, independently, a hydrogen atom, an alkyl group, a halogen atom, or a hydroxyl group, although at least one of R<sup>1</sup> to R<sup>9</sup> represents a hydroxyl group; and R<sup>10</sup> to R<sup>15</sup> each represent, independently, a hydrogen atom, an alkyl group, an alkenyl group, a cycloalkyl group or an aryl group;



wherein, R<sup>41</sup> to R<sup>43</sup> each represent, independently, a lower alkyl group, a cycloalkyl group or a lower alkoxy group; p and q each represent an integer from 1 to 3; and r, s and t each represent either 0, or an integer from 1 to 3.

11. (New) The coated substrate according to claim 10, wherein said component (A) is a fractionated resin in which fractionation treatment has been used to reduce a lower molecular weight fraction to no more than 80% by weight of a value prior to said fractionation.

12. (New) The coated substrate according to claim 10, wherein said photosensitive layer further comprises a photosensitizer (C).

13. (New) The coated substrate according to claim 10, wherein the photosensitive layer comprises both (b-1) and (b-11) as dissolution promoters.

14. (New) The coated substrate according to claim 10, wherein said component (A) has a weight average molecular weight of 2,000 to 20,000.

15. (New) The coated substrate according to claim 12, wherein the quantity of said component (C) within said photosensitive layer, relative to the combined quantity of said component (A) and said component (B) is 30% by weight or less.

16. (New) The coated substrate according to claim 10, wherein the proportion of the hydrogen atoms of the phenolic hydroxyl groups substituted with 1,2-naphthoquinonediazidesulfonyl groups within said component (A) is from 2 to 10 mol%.

17. (New) A method of forming a resist pattern comprising conducting a prebake of a coated substrate of any one of claims 10 to 16, performing selective exposure, and then performing alkali developing to form said resist pattern.

18. (New) The coated substrate according to claim 10, wherein said photosensitive layer is from 6 to 8  $\mu\text{m}$  in thickness.